

Resource Summary Report

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Oxford: PlasmaPro 100 Nano Plasma Technology

RRID:SCR_020384

Type: Tool

Proper Citation

Oxford: PlasmaPro 100 Nano Plasma Technology (RRID:SCR_020384)

Resource Information

URL: <https://plasma.oxinst.com/products/cvd/plasmapro-100-nano>

Proper Citation: Oxford: PlasmaPro 100 Nano Plasma Technology (RRID:SCR_020384)

Description: Chemical Vapour Deposition and PECVD tools for growth of 1D and 2D nanomaterials and heterostructures. PlasmaPro 100 Nano delivers performance growth of nanomaterials with in situ catalyst activation and process control, with flexible temperatures up to 1,200 degrees C.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

Availability: Commercially available

Resource Name: Oxford: PlasmaPro 100 Nano Plasma Technology

Resource ID: SCR_020384

Alternate IDs: Model_Number_100_Nano

Record Creation Time: 20220129T080350+0000

Record Last Update: 20260912T195935+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 100 Nano Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 100 Nano Plasma Technology.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.